

**REMARKS**

Claims 1-11 are pending herein.

1. Claims 1 and 7-9 were rejected under §103 over Iijima et al. (US '378 or US '772) in view of Savvides et al. This rejection is respectfully traversed for the following reasons.

The PTO has appeared to rely on Iijima et al. for disclosure of basic process features in connection with a method for continuously coating a substrate with a buffer layer, and has acknowledged that Iijima et al. fail to disclose utilizing of dual RF-ion sources, as claimed. In an attempt to attend to the deficiencies of Iijima et al., the PTO has looked to Savvides et al.

Savvides et al. describe a method of depositing a biaxially textured buffer layer by utilization of dual ion sources, notably ion sources 47 and 48 shown in FIG. 3. As illustrated, the dual ion sources, are positioned to be aimed at the same spot on the substrate. The two ion sources are provided to maintain a quality biaxial texture, while apparently improving deposition rates.

While the claimed invention also calls for use of dual RF-ion sources, the particular arrangement of the sources in the context of the claimed coating method expands the deposition zone, by orienting the sources to bombard different portions within the deposition zone (see FIG. 4, for example). This particular positioning of the ion sources has now been clarified in the present claims, reciting that the dual RF-ion sources are oriented to be aimed at and bombard different portions of the deposition zone. In addition, new claim 10 has been added to recite incorporation of a separator to isolate the ion beams from the two sources from each other. In this respect, see separator 170 shown in FIG. 4 of the present application. As stated above, Savvides et al. specifically teach orientation of ion sources to impinge upon and bombard the same portion of the deposition zone. The prior art nowhere discloses or even remotely suggests the invention as now claimed, requiring RF-ion sources oriented to be aimed at and bombard different portions of the deposition zone.

For at least the foregoing reason, Applicants submit that the presently claimed invention would not have been obvious over Iijima et al. in view of Savvides et al. Accordingly, withdrawal of the §103 rejection is respectfully requested.

2. Claim 2 was rejected in further view of Fritzemeier et al. In addition, claims 3-6 were rejected over the references noted above, further citing that the features of claims 3-6 are a matter of "design choice." Applicants submit that these rejections are deficient for the reasons advanced above, and should also be withdrawn.

Applicants respectfully submit that the present application is now in condition for allowance. Accordingly, the Examiner is requested to issue a Notice of Allowance for all pending claims.

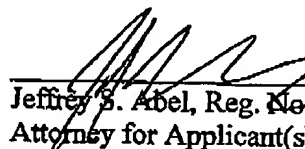
Should the Examiner deem that any further action by the Applicants would be desirable for placing this application in even better condition for issue, the Examiner is requested to contact Applicants' undersigned attorney at the number listed below.

Applicants do not believe that any additional fees are due, but if the Commissioner believes additional fees are due, the Commissioner is hereby authorized to charge any fees which may be required, or credit any overpayment, to Deposit Account Number 50-2469.

Respectfully submitted,

Date

10/19/05

  
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